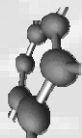


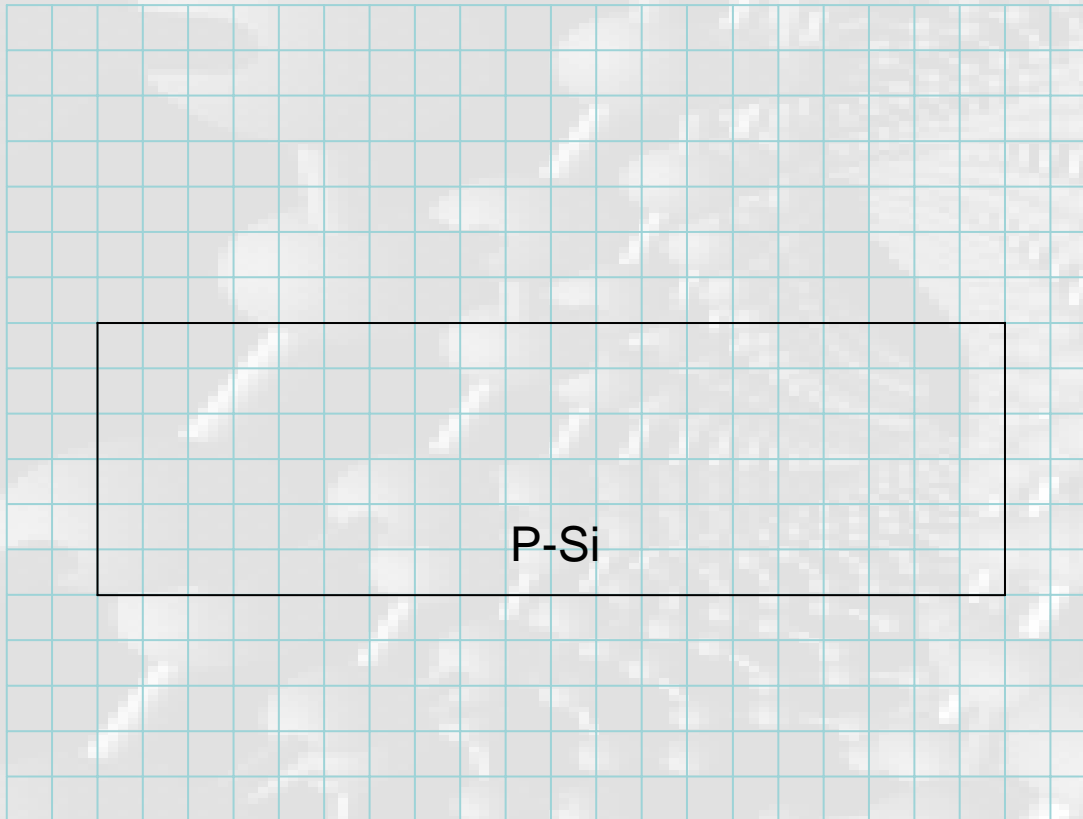
# Regras de Projeto



**GRUDE**  
Grupo de Dispositivos Eletrônicos

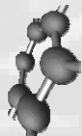
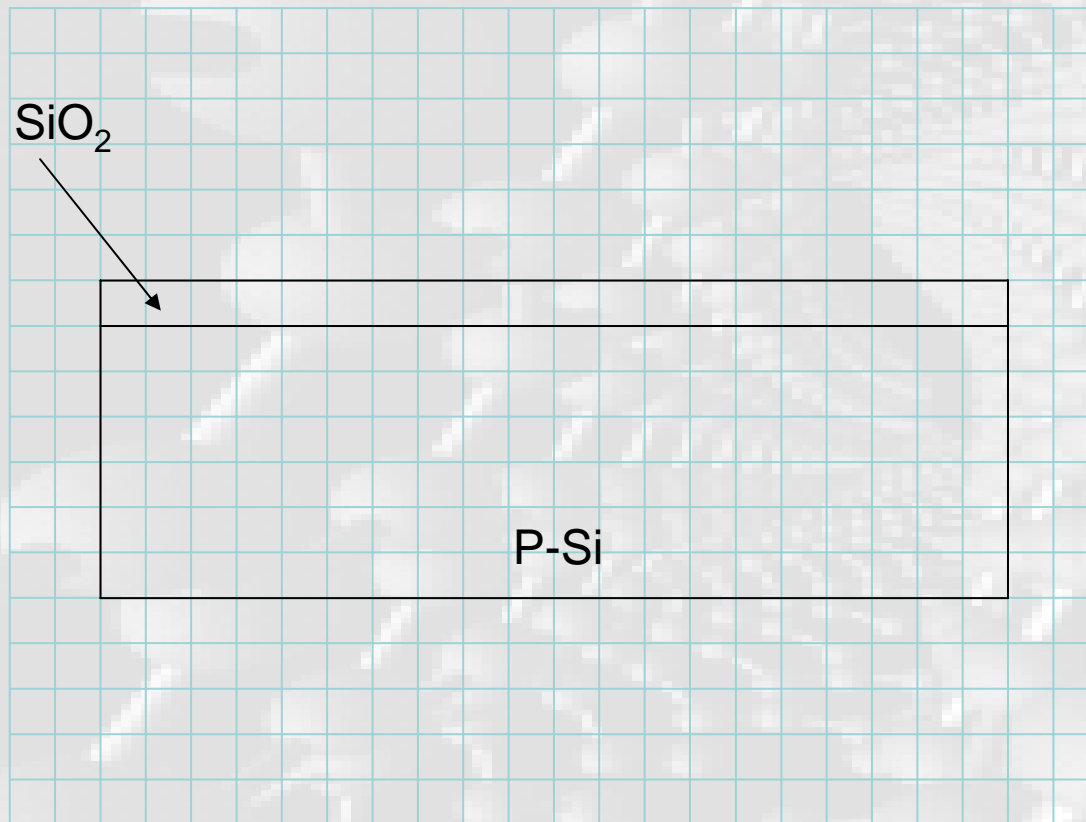
# Silício tipo p

Máscara



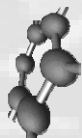
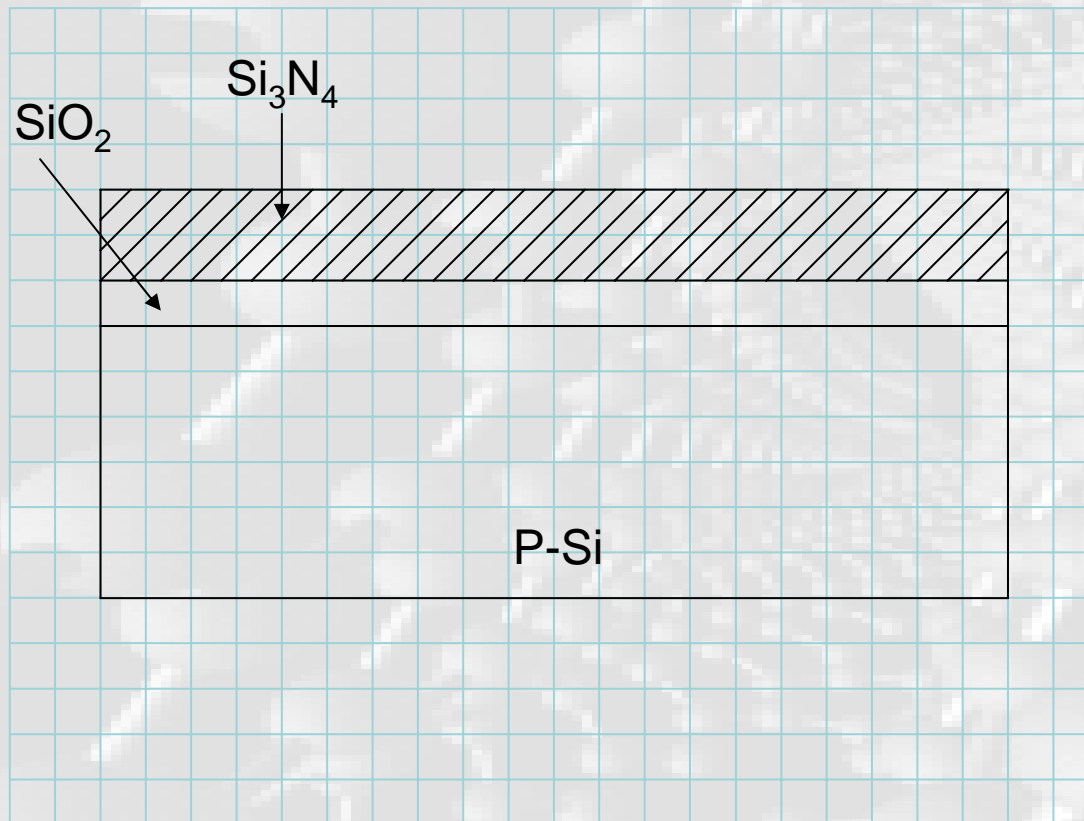
# Oxidação Seca

Máscara



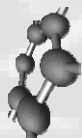
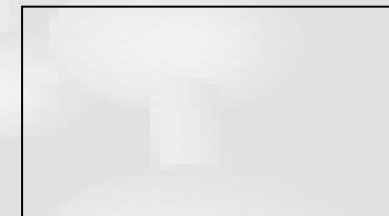
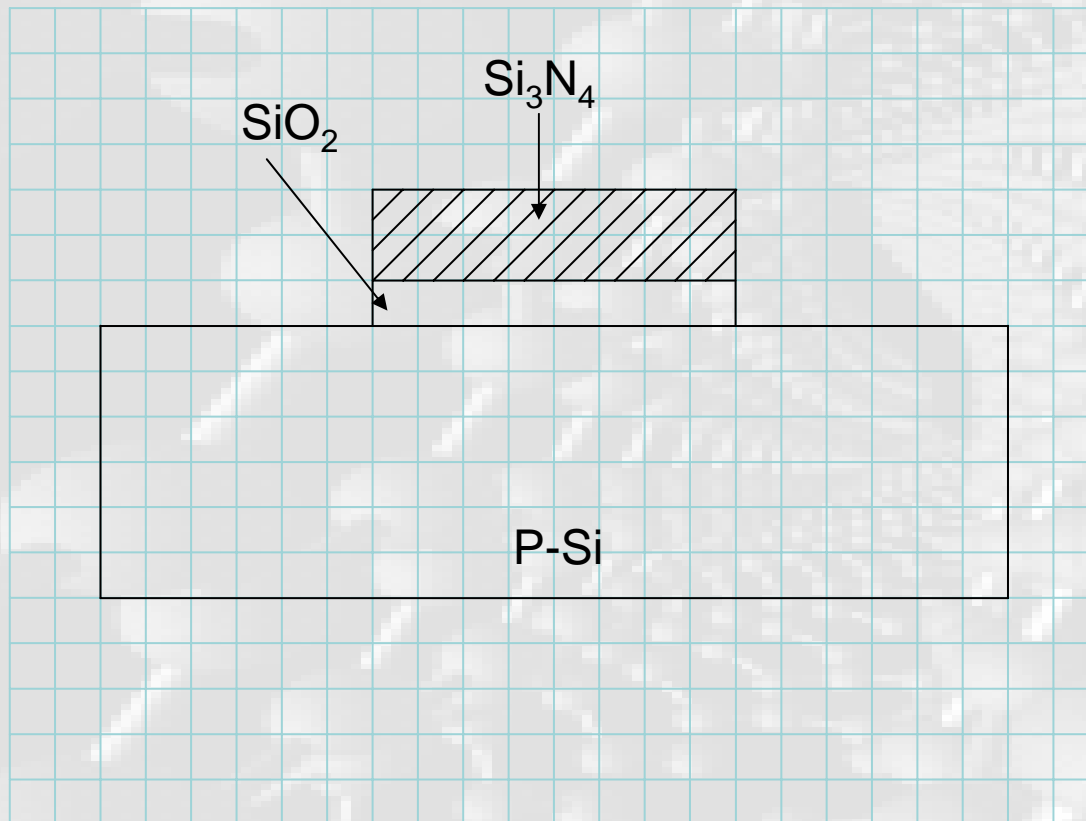
# PECVD de $\text{Si}_3\text{N}_4$

Máscara



# RIE

Máscara

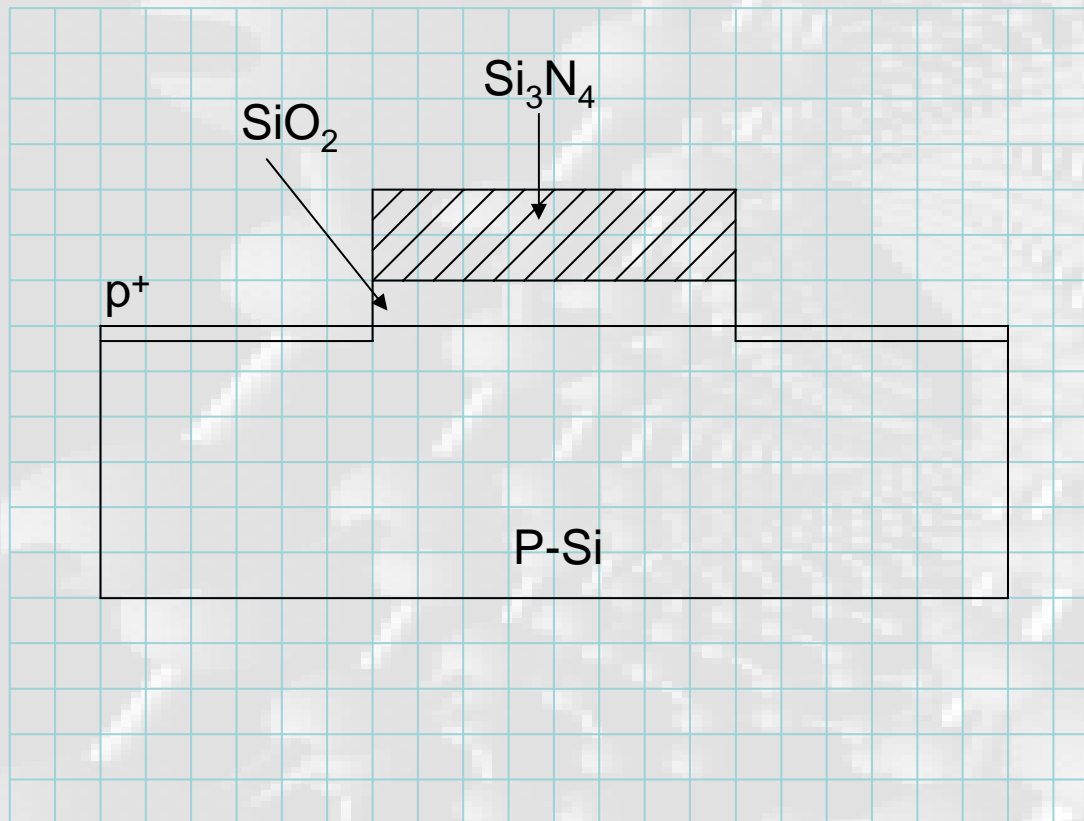


**GRUDE**

Grupo de Dispositivos Eletrónicos

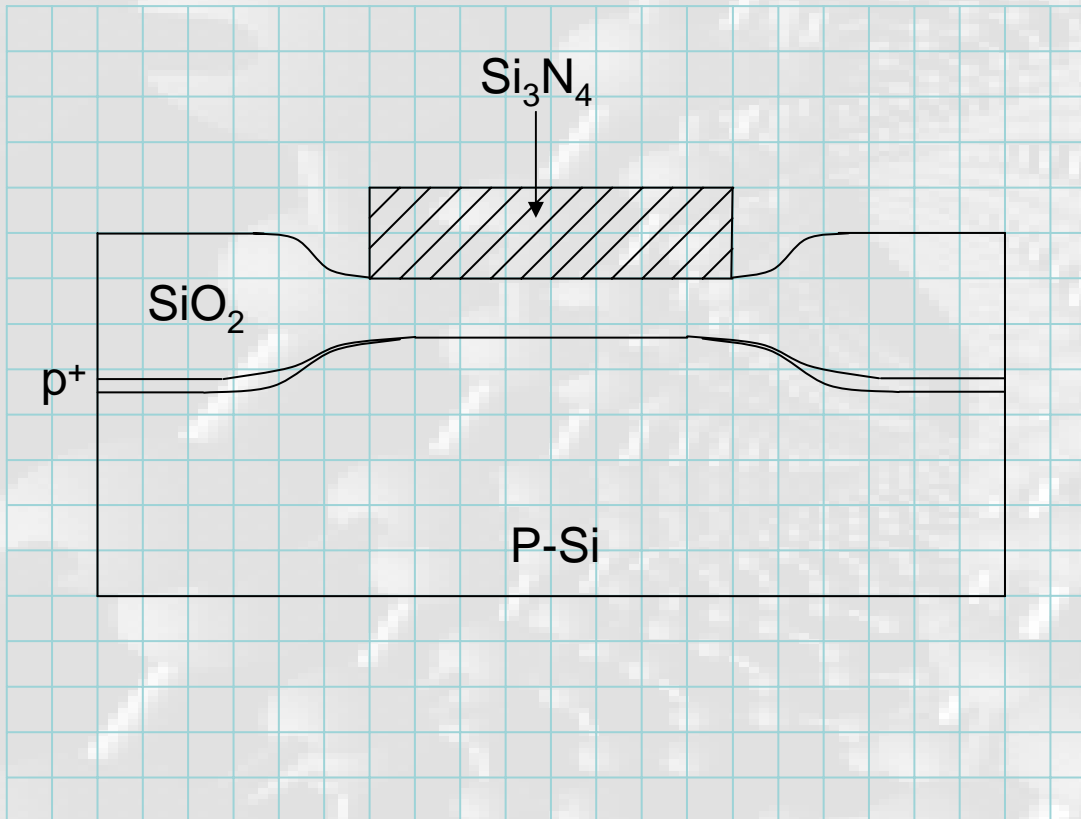
# Difusão de Boro

Máscara



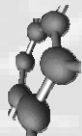
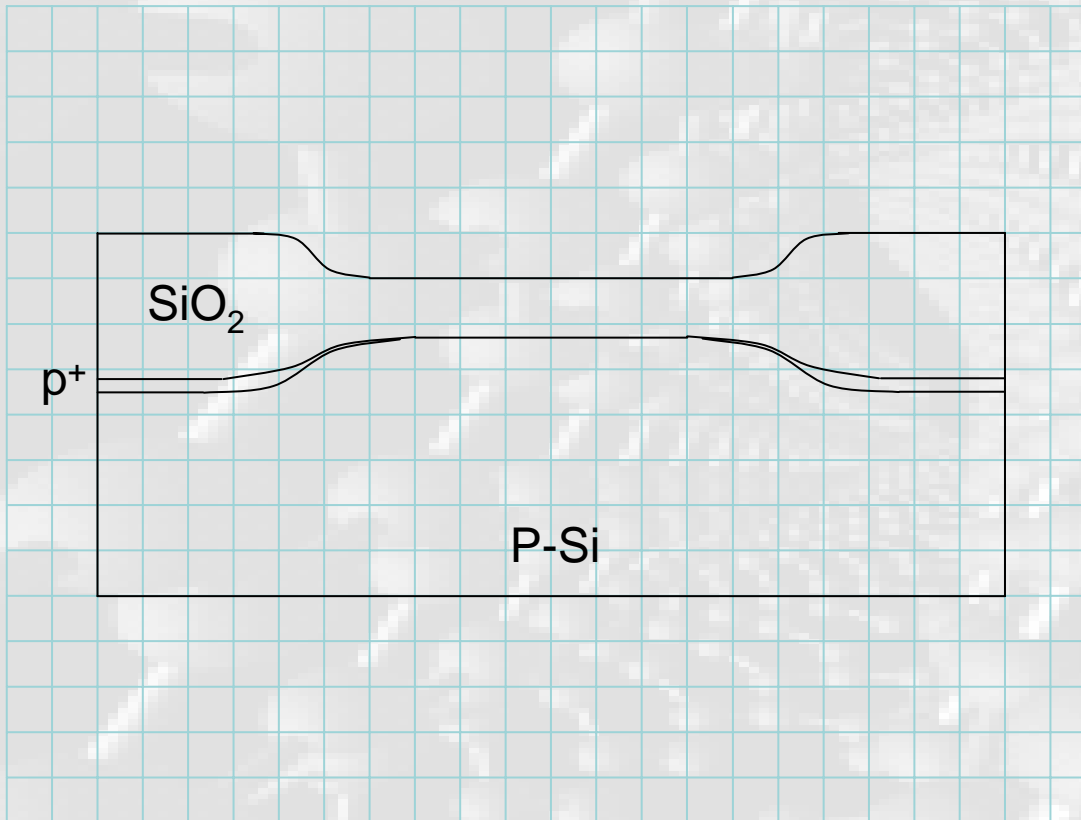
# Oxidação

Máscara



# Corrosão Química

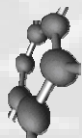
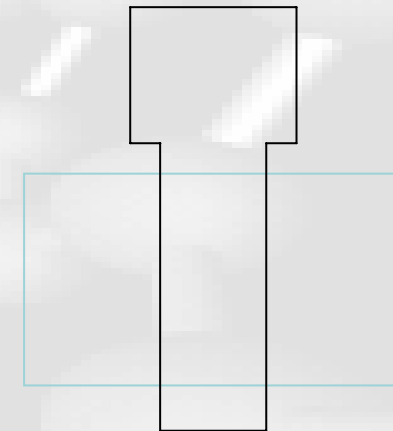
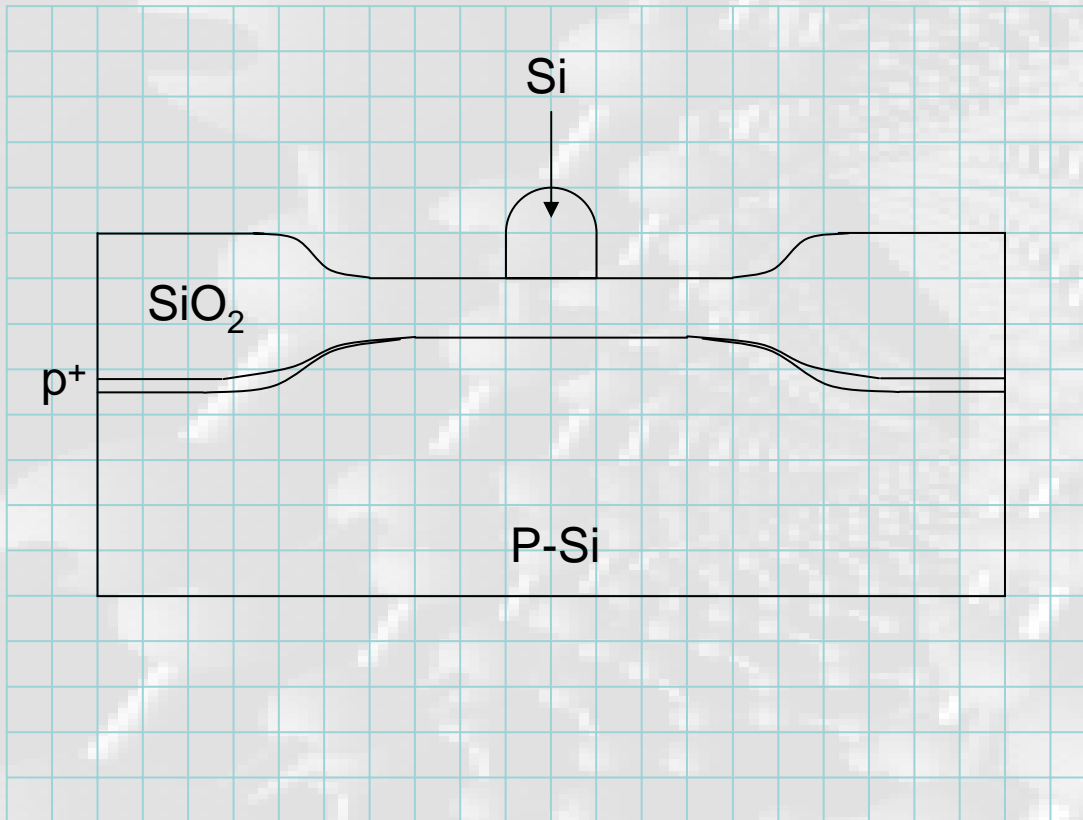
Máscara





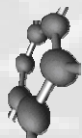
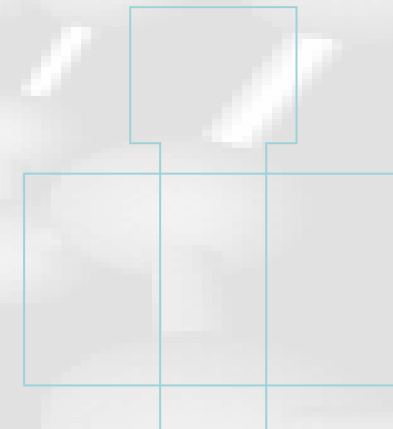
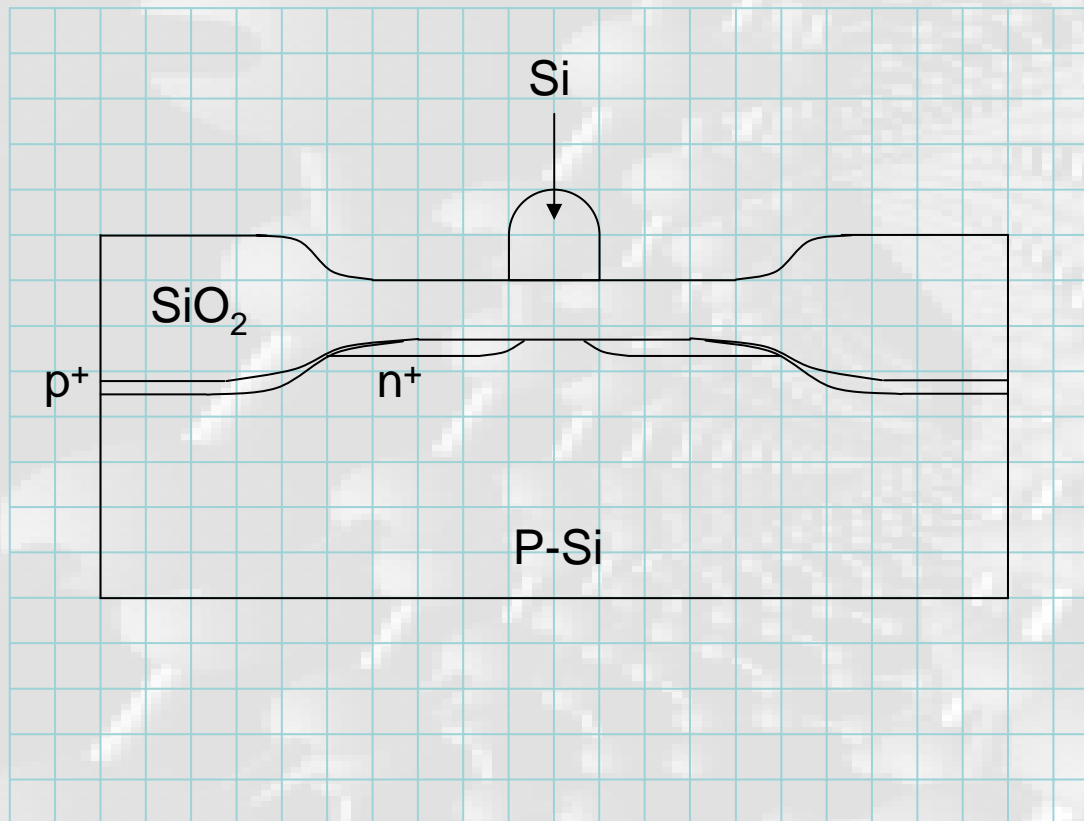
# CVD de Poli-Si

Máscara



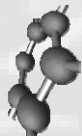
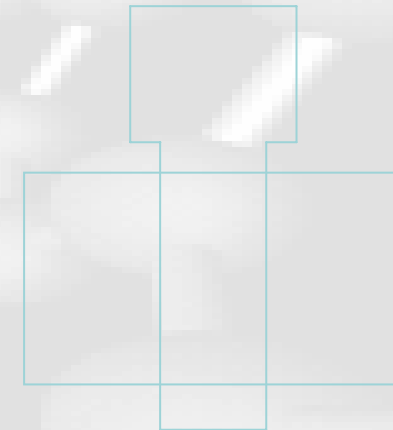
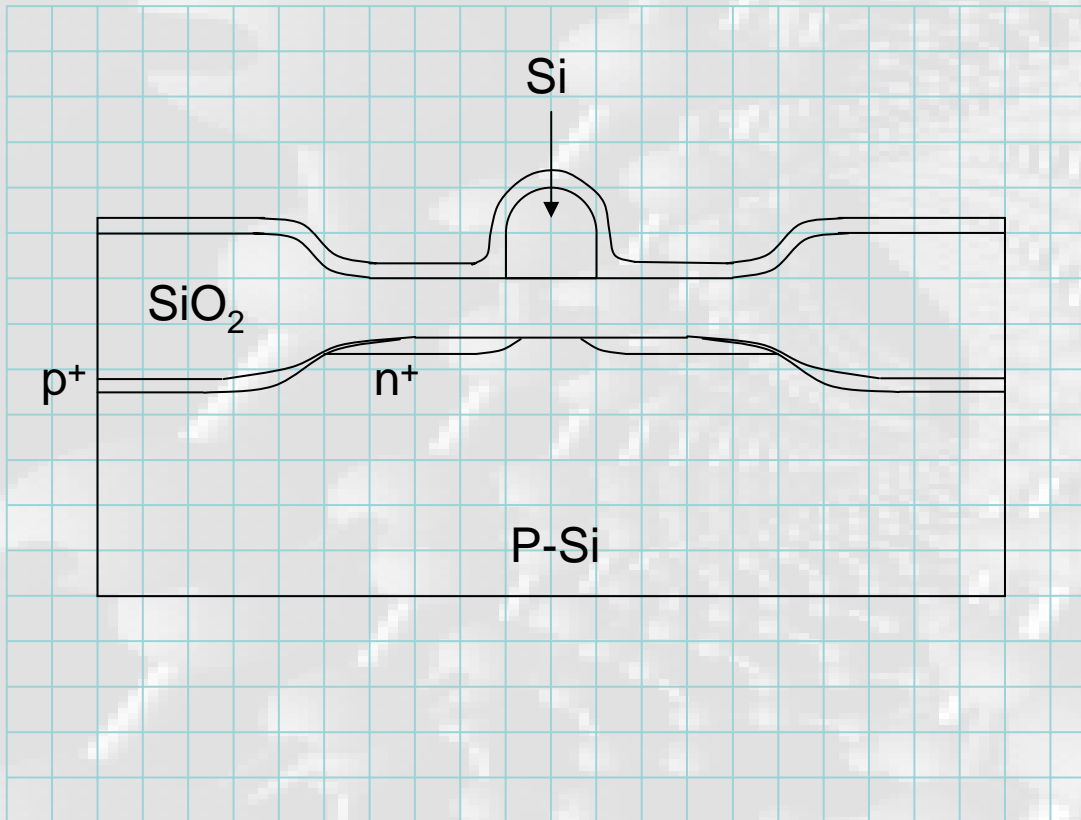
# Implantação de Fósforo

Máscara



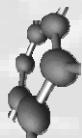
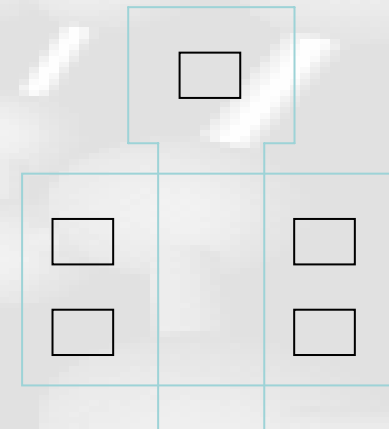
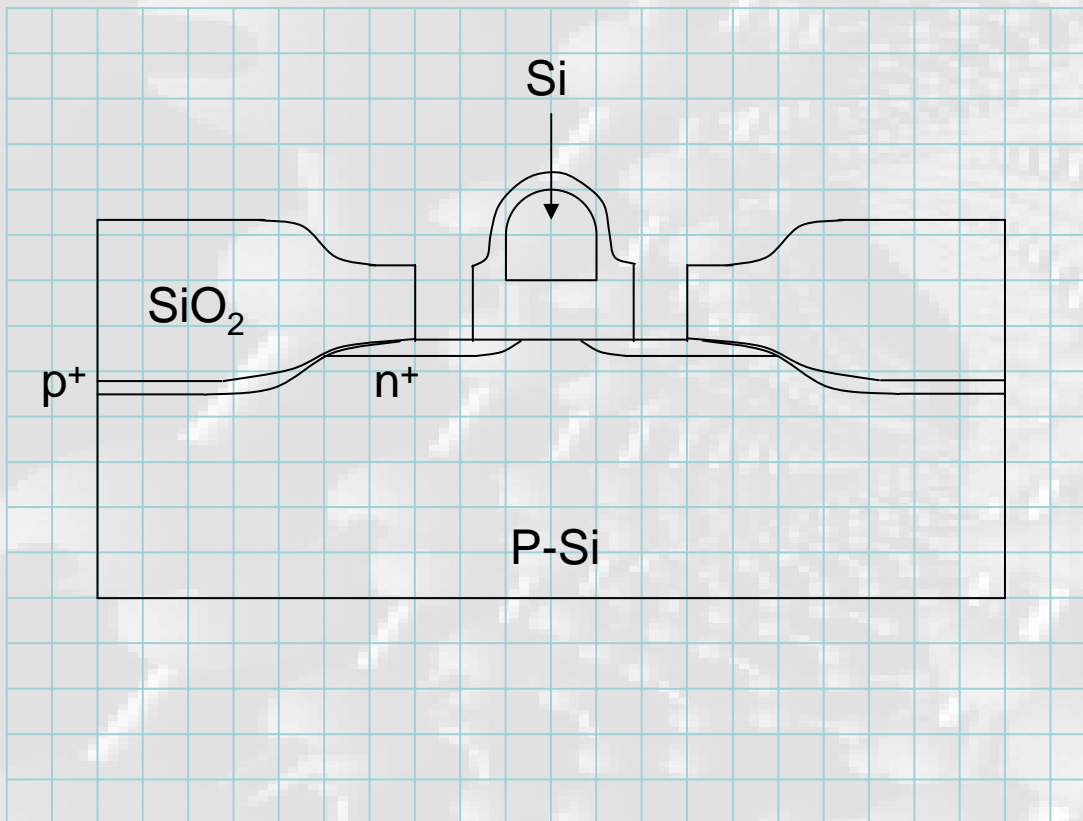
# Oxidação Térmica

Máscara



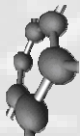
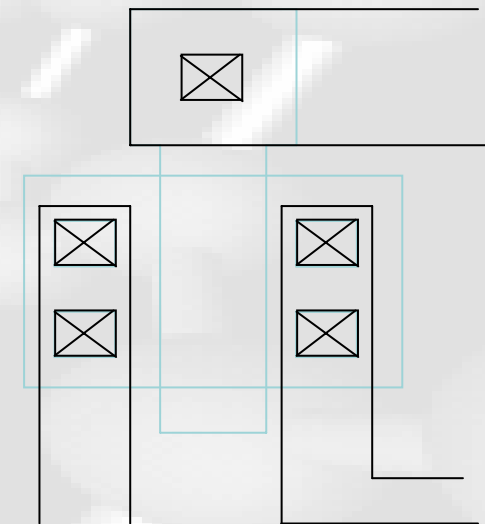
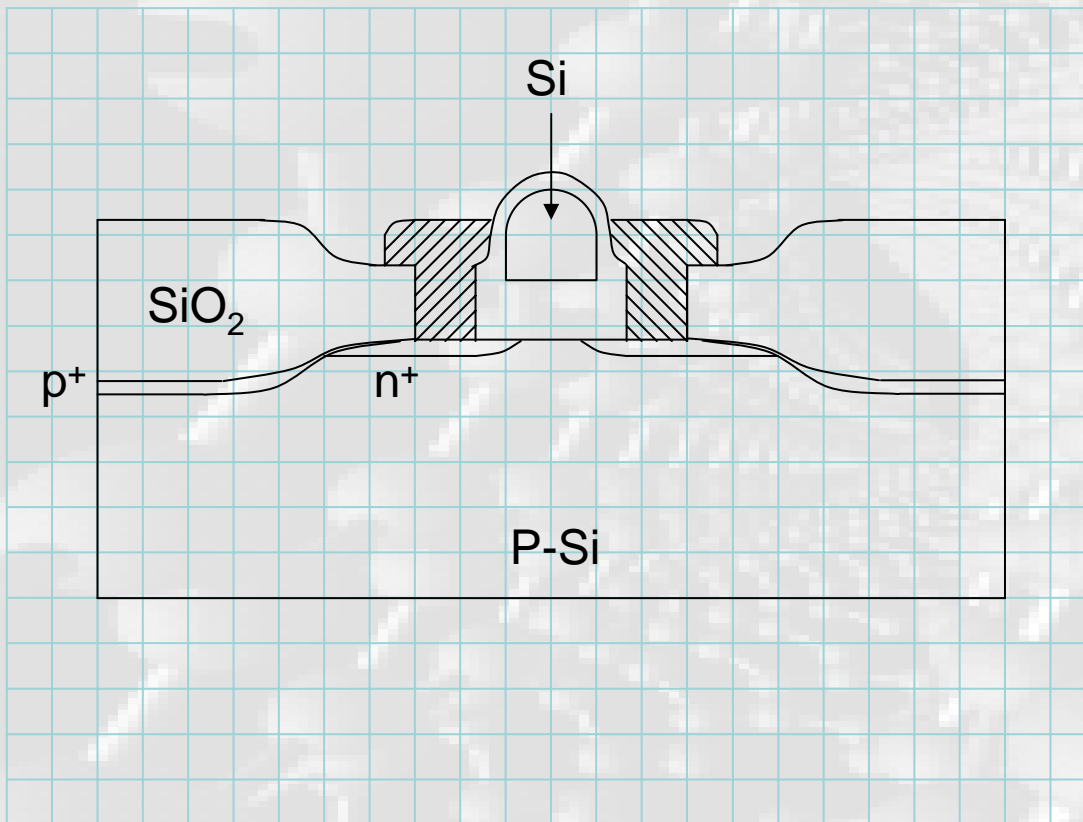
# RIE

Máscara

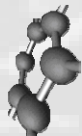
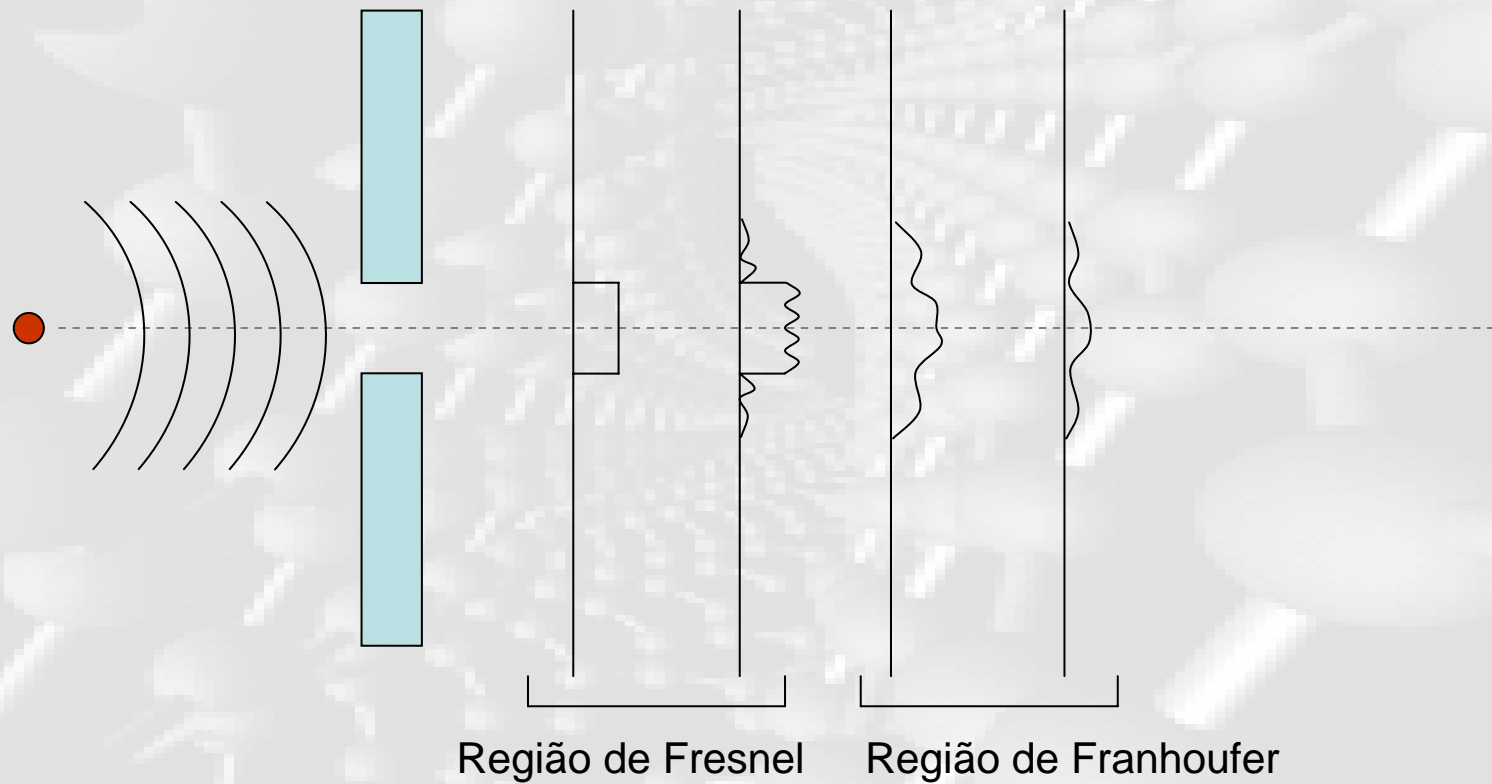


# Sputtering de Al

Máscara



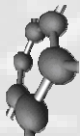
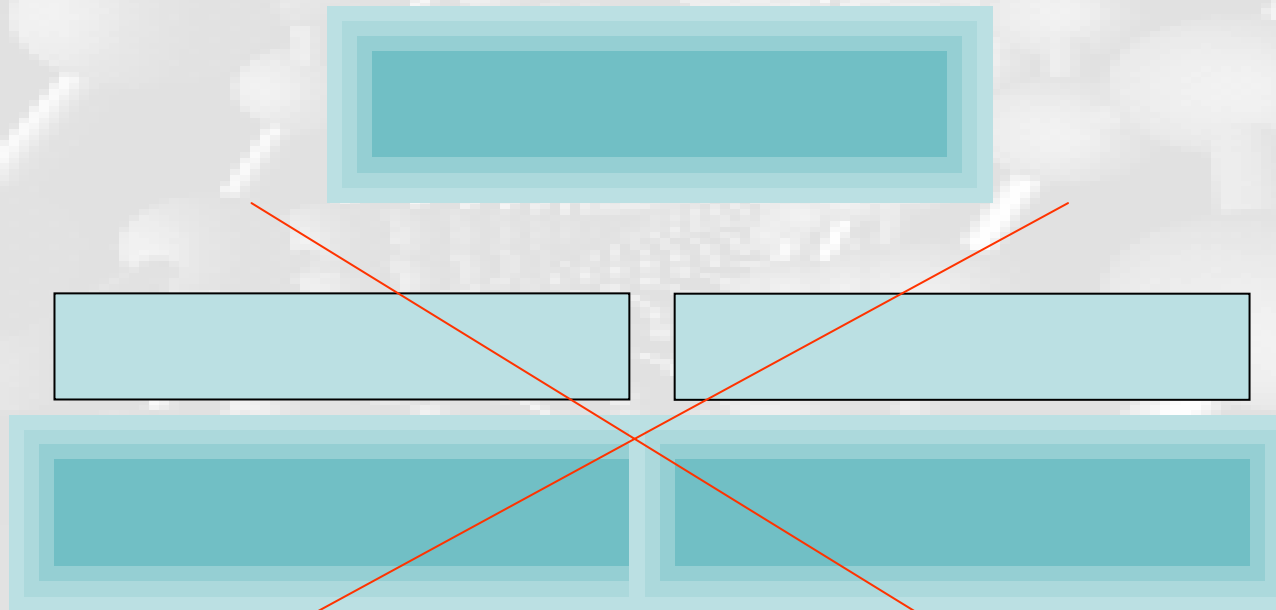
# Aberração Litográfica



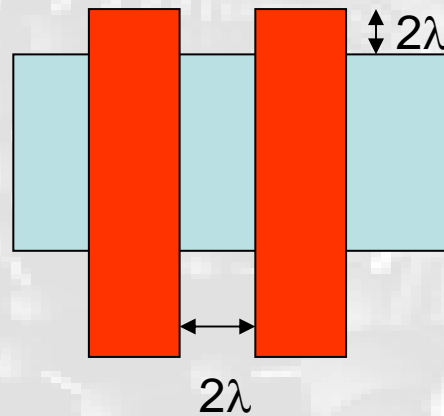
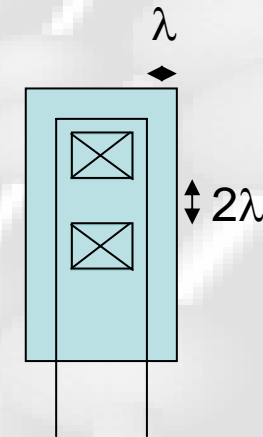
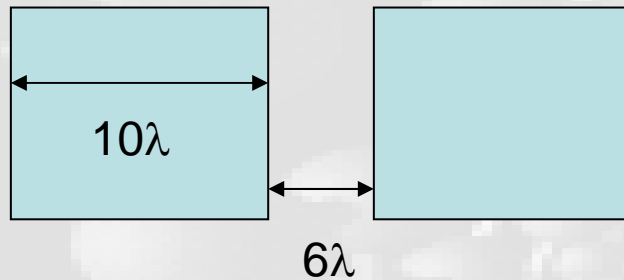
# Tamanhos Efetivos

Máscara

+ Difusão + Oxidação + Aberração + Incerteza + Canal Elétrico + ...



# Regras de projeto



Layout Design Rules  
(LDR) Mead-Conway

$$\lambda = 4-1\mu\text{m}$$